



(51) International Patent Classification:

G03F 7/20 (2006.01) G02B 5/20 (2006.01)
G21K 1/06 (2006.01) G02B 5/08 (2006.01)
G03F 1/14 (2006.01) C01B 31/04 (2006.01)

(21) International Application Number:

PCT/EP2011/054057

(22) International Filing Date:

17 March 2011 (17.03.2011)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

61/358,645 25 June 2010 (25.06.2010) US
61/362,981 9 July 2010 (09.07.2010) US

(71) Applicant (for all designated States except US): **ASML NETHERLANDS B.V.** [NL/NL]; De Run 6501, NL-5504 DR Veldhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **YAKUNIN, Andrei** [RU/NL]; Oudaen 117, NL-5653 KD Eindhoven (NL). **BANINE, Vadim** [NL/NL]; Eendracht 21, NL-5751 SB Deurne (NL). **LOOPSTRA, Erik** [NL/NL]; Lakerstraat 32-34, NL-5613 ES Eindhoven (NL). **VAN DER SCHOOT, Harmen** [NL/NL]; Klein Brabant 20, NL-5262 RK Vught (NL). **STEVENS, Lucas** [NL/NL]; Grassijsje 15, NL-5658 EE Eindhoven (NL). **VAN KAMPEN, Maarten** [NL/NL]; Venbergsemolen 179, NL-5612 DZ Eindhoven (NL).

(74) Agent: **SLENDERS, Peter**; De Run 6504, NL-5504 DR Veldhoven (NL).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

- with international search report (Art. 21(3))
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (Rule 48.2(h))

(54) Title: LITHOGRAPHIC APPARATUS AND METHOD

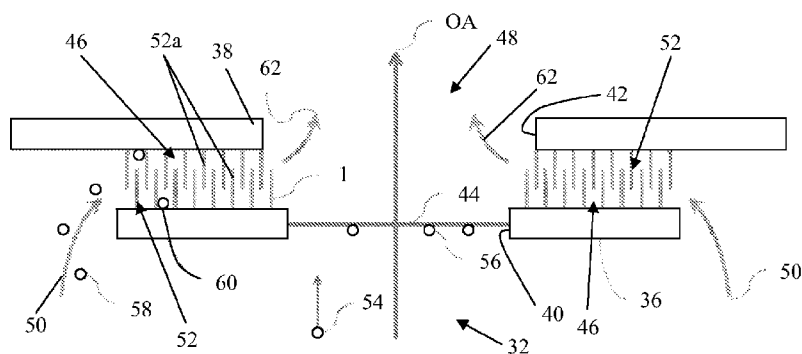


Figure 3

(57) Abstract: A lithographic apparatus includes a radiation source configured to produce a radiation beam, and a support configured to support a patterning device. The patterning device is configured to impart the radiation beam with a pattern to form a patterned radiation beam. A chamber is located between the radiation source and patterning device. The chamber contains at least one optical component configured to reflect the radiation beam, and is configured to permit radiation from the radiation source to pass therethrough. A membrane (44) is configured to permit the passage of the radiation beam, and to prevent the passage of contamination particles (54) through the membrane. A particle trapping structure (52) is configured to permit gas to flow along an indirect path from inside the chamber to outside the chamber. The indirect path is configured to substantially prevent the passage of contamination particles (58) from inside the chamber to outside the chamber.